



Attorney's Docket No.: 042390P7195

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)
)
Steven N. Towle et al.)
)
U.S. Serial No: 09/639,625)
)
Filed: August 15, 2000)
)
For: Plasma Induced Depletion of)
Fluorine From Surfaces of)
Fluorinated Low-K Dielectric)
Materials)

Examiner: Douglas W. Owens

Art Unit: 2811

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage in an envelope addressed to the Commissioner for Patents, PO Box 1450, Alexandria, Virginia 22313-1450

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TERESA EDWARDS

Name of Person Mailing Correspondence

Teresa Edwards

Signature

7/17/03

Date

DECLARATION UNDER 37 C.F.R. §1.131

Sir:

I, Ebrahim Andideh, declare the following:

1. I am an inventor of the above captioned patent application ("the Application") and an inventor of the subject matter described therein.
2. At least prior to February 25, 2000, the invention claimed in the Application had been conceived and reduced to practice in this country.
3. As evidence of invention, attached hereto as Exhibit A is an Intel Invention Disclosure Form entitled: "Plasma-induced depletion of fluorine from surfaces of fluorinated low-k dielectric materials," which in its unredacted form, is dated prior to February 25, 2000.

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4. I declare, to the best of my knowledge, that all statements made in this document are true, and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the above-identified patent application or any patent issued thereon.

Date: July 11, 2003 Ebrahim Andideh
Name: Ebrahim Andideh